

## AMENDMENTS TO THE CLAIMS

### **Listing of Claims.**

1. (Currently Amended) An apparatus for removing pollution from a substrate, said apparatus comprising:

a) a rotation mechanism for rotating said substrate in a horizontal plane;

b) an injection mechanism, comprising

[[a)]] b-1) a liquid discharging mechanism for discharging liquid into an open space, and

[[b)]] b-2) a gas discharging mechanism for discharging gas in a vicinity of said liquid in said open space to convert said liquid into liquid droplets and generate mixture of said gas and said liquid droplets,

said mixture of said gas and said liquid droplets being applied to a surface of said substrate to clean said surface of said substrate,

c) a support member for supporting said injection mechanism in such a way that said injection mechanism is capable of injecting said mixture toward said surface of said substrate;  
and

d) a moving mechanism for shifting said support member from a standby position to a cleaning start position of said substrate.

2. (Original) The apparatus in accordance with claim 1, wherein

said liquid and said gas are collided with each other in said open space to obtain said mixture of said gas and said liquid droplets.

3. (Original) The apparatus in accordance with claim 1, wherein

said mixture is obtained by discharging one of said liquid and said gas into a jet flow of the other of said liquid and said gas.

4. (Original) The apparatus in accordance with claim 1, wherein

said liquid discharging mechanism has a liquid outlet through which said liquid is discharged,

said gas discharging mechanism has a gas outlet through which said gas is discharged, and

an angle between a center axis line of said liquid outlet and a center axis line of said gas outlet is not less than 0 degrees and not more than 110 degrees.

5. (Currently Amended) An apparatus for removing pollution from a substrate, said apparatus comprising:

a) a rotation mechanism for rotating said substrate in a horizontal plane;

[[a)]] b) first and second supply paths for supplying liquid and gas, respectively;

[[b)]] c) a nozzle coupled to said first and second supply paths for mixing said liquid with said gas to obtain a cleaning fluid and applying said cleaning fluid onto a surface to said substrate, comprising

~~b-1)~~ c-1) a liquid outlet through which said liquid is discharged in an open space, and

~~b-2)~~ c-2) a gas outlet through which said gas is discharged into said liquid in said open space to convert said liquid into liquid droplets,  
said cleaning fluid being mixture of said gas and said liquid droplets in said space,

d) a support member for supporting said nozzle: and

e) a moving mechanism for shifting said nozzle from a standby position to a cleaning start position of said substrate.

6. (Original) The apparatus in accordance with claim 5, wherein

said liquid and said gas are collided with each other in said open space to obtain said mixture of said gas and said liquid droplets.

7. (Original) The apparatus in accordance with claim 5, wherein

said mixture is obtained by discharging one of said liquid and said gas into a jet flow of the other of said liquid and said gas.

8. (Original) The apparatus in accordance with claim 5, wherein

an angle between a center axis line of said liquid outlet and a center axis line of said gas outlet is not less than 0 degrees and not more than 110 degrees.

9. (Currently Amended) The apparatus in accordance with claim 5, further comprising:

[[c)]] f) a controller for controlling said first and second supply paths to start supply of said liquid after supply of said gas is started.

10. (Original) The apparatus in accordance with claim 9, wherein

said controller is operable to control said first and second supply paths to stop supply of said liquid after supply of said gas is stopped.

Claims 11 and 12 (Cancelled)

13. (New) An apparatus for removing pollution from a substrate, said apparatus comprising:

a) a rotation mechanism for rotating said substrate in a horizontal plane;

b) an injection mechanism; comprising

b-1) a liquid discharging mechanism for discharging liquid into an open space,

and

b-2) a gas discharging mechanism for discharging gas in a vicinity of said liquid in said open space to convert said liquid into liquid droplets and generate mixture of said gas and said liquid droplets,

said mixture of said gas and said liquid droplets being applied to a surface of said substrate from a position opposite to said surface of said substrate, to clean said surface of said substrate, and

c) a support member for supporting said injection mechanism in such a way that said injection mechanism is capable of injecting said mixture toward said surface of said substrate.

14. (New) The apparatus in accordance with claim 13 [[11]], wherein  
said liquid and said gas are collided with each other in said open space to obtain said mixture of said gas and said liquid droplets.

15. (New) The apparatus in accordance with claim 13 [[11]], wherein  
said mixture is obtained by discharging one of said liquid and said gas into a jet flow of the other of said liquid and said gas.

16. (New) The apparatus in accordance with claim 13 [[11]], wherein  
said liquid discharging mechanism has a liquid outlet through which said liquid  
is discharged,

said gas discharging mechanism has a gas outlet through which said gas is discharged,  
and  
an angle between a center axis line of said liquid outlet and a center axis line of said gas outlet is  
not less than 0 degrees and not more than 110 degrees.